

Amendments to the Specification:

Please replace the title as follows:

~~EXPOSURE APPARATUS, EXPOSURE METHOD, DEVICE PRODUCING METHOD,~~
~~AND OPTICAL COMPONENT~~
EXPOSURE APPARATUS, EXPOSURE METHOD, METHOD FOR PRODUCING
DEVICE, AND OPTICAL PART

Please replace the paragraph beginning on page 6, line 5, with the following rewritten paragraph:

In order to achieve the objects as described above, the present invention adopts the following constructions corresponding to Figs. 1 to 21 as illustrated in embodiments. ~~However, parenthesized symbols affixed to respective elements merely exemplify the elements by way of example, with which it is not intended to limit the respective elements.~~

Please replace the paragraph beginning on page 6, line 12, with the following rewritten paragraph:

According to a first aspect of the present invention, there is provided an exposure apparatus (~~EX~~) which exposes a substrate (~~P~~) by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) through a liquid (~~L~~); the exposure apparatus comprising a projection optical system (~~PL~~) which projects an image of a pattern onto the substrate; and a substrate table (~~PT~~) which holds the substrate (~~P~~); wherein a member (~~30~~), at least a part of a surface (~~30A~~) of which is liquid-repellent, is provided exchangeably on the substrate table.

Please replace the paragraph beginning on page 7, line 12, with the following rewritten paragraph:

According to a second aspect of the present invention, there is provided an exposure method for performing liquid immersion exposure for a substrate (~~P~~) by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) via a projection optical system (~~PL~~) and a liquid (~~1~~); the exposure method comprising holding the substrate (~~P~~) with a substrate-holding member (~~30~~), the substrate-holding member (~~30~~) having a flat portion (~~30A~~) which is disposed around the substrate (~~P~~) and which is substantially flush with a surface of the substrate (~~P~~); loading the substrate-holding member (~~30~~) to a substrate stage (~~PST, PT~~), the substrate-holding member (~~30~~) holding the substrate (~~P~~); performing the liquid immersion exposure for the substrate (~~P~~) loaded onto the substrate stage (~~PST, PT~~); and unloading the substrate-holding member (~~30~~) with which the substrate (~~P~~) is held from the substrate stage (~~PST, PT~~) after completion of the liquid immersion exposure.

Please replace the paragraph beginning on page 9, line 3, with the following rewritten paragraph:

According to a third aspect of the present invention, there is provided an exposure apparatus (~~EX~~) which exposes a substrate (~~P~~) by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) through a liquid (~~1~~); the exposure apparatus comprising a projection optical system (~~PL~~) which projects an image of a pattern onto the substrate; and a movable stage (~~PST~~) which is movable relative to the projection optical system (~~PL~~); wherein a liquid-repellent member (~~30, PH, 300, 400, 500~~), at least a part of which is liquid-repellent, is provided on the movable stage (~~PST~~), and the liquid-repellent member is exchangeable.

Please replace the paragraph beginning on page 10, line 2, with the following rewritten paragraph:

According to a fourth aspect of the present invention, there is provided an exposure

method for performing liquid immersion exposure for a substrate (~~P~~) by radiating an exposure light beam (~~EL~~) onto the substrate (~~P~~) through a liquid (~~1~~); the exposure method comprising supplying the liquid (~~1~~) to at least a part of a surface of the substrate (~~P~~); and performing the liquid immersion exposure for the substrate by radiating the exposure light beam (~~EL~~) onto the substrate (~~P~~) through the liquid; wherein a part (~~30, 300, 400, 500~~) of the exposure apparatus, which is different from the substrate for which the liquid is supplied, is liquid-repellent, and the liquid-repellent part (~~30, 300, 400, 500~~) of the exposure apparatus is exchanged depending on deterioration of liquid repellence thereof.

Please replace the paragraph beginning on page 11, line 2, with the following rewritten paragraph:

According to a fifth aspect of the present invention, there is provided an optical part (~~650, 652, 654~~) to be provided on a substrate stage of a projection exposure apparatus (~~EX~~) which illuminates a mask (~~M~~) with an exposure light beam (~~EL~~) and transfers a pattern of the mask through a liquid (~~1~~) onto a substrate (~~P~~) held by the substrate stage by using a projection optical system; the optical part comprising a light irradiated surface (~~660~~) which is irradiated with the exposure light beam; an adhesive particulate layer (~~662~~) which comprises a particulate layer composed of at least one of silicon dioxide, magnesium fluoride, and calcium fluoride, and formed on the light irradiated surface; and a water-repellent film (~~664~~) which is composed of an amorphous fluororesin and formed on a surface of the adhesive particulate layer.

Please replace the paragraph beginning on page 13, line 6, with the following rewritten paragraph:

According to a sixth aspect of the present invention, there is provided an optical part

~~(650, 652, 654)~~ to be provided on a substrate stage ~~(PST)~~ of a projection exposure apparatus for illuminating a mask ~~(M)~~ with an exposure light beam ~~(EL)~~ and transferring a pattern of the mask through a liquid ~~(L)~~ onto a substrate held by the substrate stage ~~(PST)~~ by using a projection optical system ~~(PL)~~; the optical part comprising a light irradiated surface ~~(660)~~ which is irradiated with the exposure light beam; an adhesive surface ~~(668)~~ which is formed on the light irradiated surface; and a water-repellent film ~~(664)~~ which is composed of an amorphous fluoro-resin and formed on the adhesive surface. In the optical part of this aspect, it is preferable that the adhesive surface is a surface subjected to etching with hydrogen fluoride.

Please replace the paragraph beginning on page 15, line 5, with the following rewritten paragraph:

According to a seventh aspect of the present invention, there is provided a projection exposure apparatus ~~(EX)~~ which illuminates a mask ~~(M)~~ with an exposure light beam ~~(EL)~~ and transfers a pattern of the mask through a liquid onto a substrate held by a substrate stage ~~(PST)~~ by using a projection optical system ~~(PL)~~; the projection exposure apparatus comprising, on the substrate stage, an optical part including a light irradiated surface ~~(660)~~ which is irradiated with the exposure light beam; an adhesive particulate layer ~~(662)~~ which is formed on the light irradiated surface; and a water-repellent film ~~(664)~~ which is composed of an amorphous fluoro-resin and formed on a surface of the adhesive particulate layer.

Please replace the paragraph beginning on page 16, line 16, with the following rewritten paragraph:

According to an eighth aspect of the present invention, there is provided an optical part ~~(300, 400, 500, 650, 652, 654)~~ comprising a part body ~~(660)~~ which has a light irradiated

surface; a particulate layer (662)-which is formed of at least one particulate selected from the group consisting of silicon dioxide, magnesium fluoride, and calcium fluoride, and formed on the light irradiated surface; and a water-repellent film (664)-which is formed of an amorphous fluororesin, on a surface of the particulate layer. The water-repellent film is strongly connected to the light irradiated surface by the aid of the particulate layer. Therefore, the present invention is extremely useful for the way of use including, for example, optical sensors and lenses to be used in the liquid or vapor atmosphere.

Please replace the paragraph beginning on page 17, line 5, with the following rewritten paragraph:

According to a ninth aspect of the present invention, there is provided an optical part (~~300, 400, 500, 650, 652, 654~~) comprising a part body (660)-which has a light irradiated surface; an adhesive surface (668)-which is formed by etching on the light irradiated surface; and a water-repellent film (664)-which is formed of an amorphous fluororesin, on the adhesive surface. The water-repellent film is strongly connected to the light irradiated surface by the aid of the particulate layer. Therefore, the present invention is extremely useful for the way of use including, for example, optical sensors and lenses to be used in the liquid or vapor atmosphere.